Supporting Information

Wafer-Scale Si-Based Metal-Insulator-Semiconductor Photoanodes for Water Oxidation Fabricated Using Thin Film Reactions and Multiple-layer Electrodeposited Catalysts

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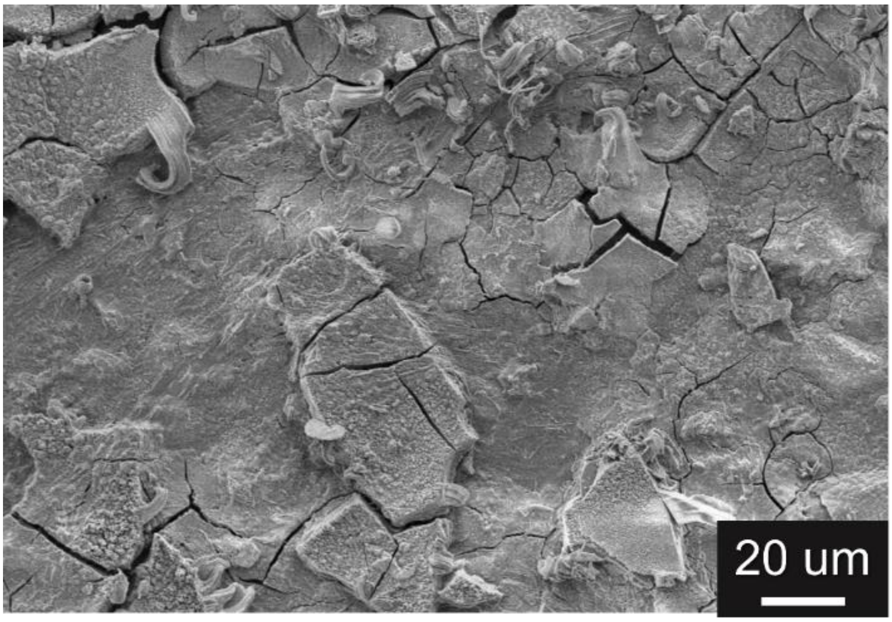

Figure S1. Plan-view SEM image of electrodeposited NiFe film on Ni plate.

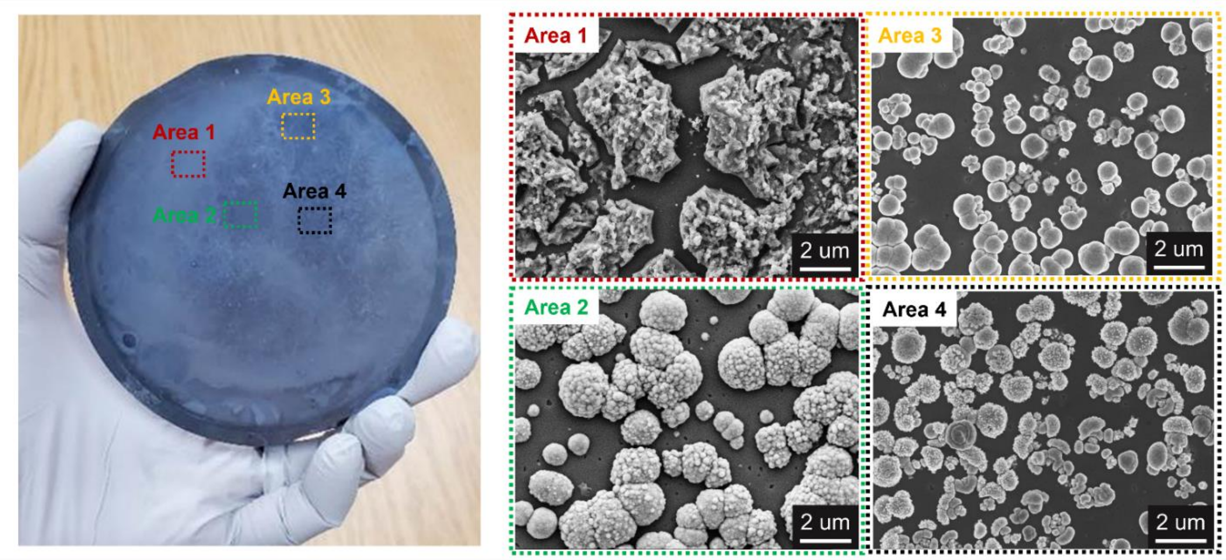

Figure S2. Photograph of wafer-scale (4-inch) spiked NiFe/Ni/SiO_2/Si photoanode and corresponding SEM images of wafer-scale (4-inch) spiked NiFe/Ni/SiO_2/Si photoanode in different regions.